

# Tuesday Morning, October 23, 2018

## Exhibitor Technology Spotlight Workshops

### Room Hall A - Session EW-TuB

#### Exhibitor Technology Spotlight Session I

**Moderator:** Christopher Moffitt, Kratos Analytical Inc

**10:20am EW-TuB-2 IMPULSE HIPIMS Power Supply with Positive Pulse Option Advantages, *Jason Hrebik*, Kurt J. Lesker Company**

HIPIMS is an ionized PVD technique that produces a high density, high performance films. The extreme power densities in HIPIMS create a higher ionized plasma that creates a very high energy of material being deposited onto the substrate.

The IMPULSE HIPIMS supply offers a cost effective solution for HIPIMS research and process development. The IMPULSE is a scalable option for higher power applications ideal for production application scale up.

The supplies broad range of parameter adjustment along with its positive kick pulse option, provide the tools necessary to tune each process for ideal performance. This presentation will share examples of applications and performance data to support the many advantages of the IMPULSE power supply. The available configurations and examples of ideal operating parameters will be shared.

**10:40am EW-TuB-3 Choosing the Proper Equipment for Vacuum Heat Treatment, *Rachael Stene*, Across International**

Selecting the proper equipment is the first step in completing a successful process. There are several factors to consider such as target temperature, required heating rate to achieve a certain time to temperature, desired vacuum level, sample size, chemistry of the system's atmosphere, and more. Here, we elaborate on the many aspects which may be involved in your application, helping you select the perfect components for the operation. Across International's line of material processing equipment offers several advantages and comes with many helpful features, which sets us apart. We'll elaborate on these factors and the AI advantage in this presentation.

## Author Index

**Bold page numbers indicate presenter**

— H —

Hrebik, J: EW-TuB-2, **1**

— S —

Stene, R: EW-TuB-3, **1**